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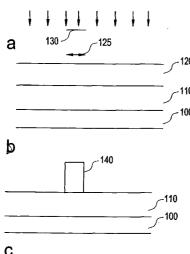
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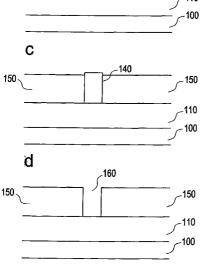
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#### (54) Title: BRIGHT FIELD IMAGE REVERSAL FOR CONTACT HOLE PATTERNING



(57) Abstract: A method of forming a small contact hole (160) uses a bright field mask (130) to form a small cylinder (140) in a positive resist layer (120) after exposure and developing. A negative resist layer (150) is formed around the small cylinder, and then etched or polished back to leave a top portion of the small cylinder exposed above the negative resist layer. The negative resist layer and the small cylinder (positive resist) are flood exposed to light, and then subject to a developer. What remains is a small contact hole (160) located where the small cylinder was previously located.







patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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## INTERNATIONAL SEARCH REPORT

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A. CLASSIFICATION OF SUBJECT MATTER IPC 7 H01L21/027										
	o International Patent Classification (IPC) or to both national class	ification and IPC								
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Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched										
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C. DOCUMI	ENTS CONSIDERED TO BE RELEVANT									
Category °	Citation of document, with indication, where appropriate, of the	relevant passages	Relevant to claim No.							
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